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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of:

Kim *et al.*

Appl. No.: 10/784,806

Filed: February 24, 2004

For: Novel Monomers Containing an Oxepan-2-One Group, Photoresist Compositions Comprising Polymers Prepared from the Monomers, Methods for Preparing the Compositions, and Methods for Forming Photoresist Patterns Using the Compositions

Confirmation No.: 1185

Art Unit: 1752

Examiner: *To Be Assigned*

Atty. Docket: 2236.0090000/JUK/SMW

Information Disclosure Statement Under 37 C.F.R. § 1.97(b)

Commissioner for Patents
PO Box 1450
Alexandria, VA 22313-1450

Sir:

Listed on accompanying Form PTO-1449 are documents that may be considered material to the examination of the captioned application, in compliance with the duty of disclosure requirements of 37 C.F.R. §§ 1.56, 1.97 and 1.98.

No copies of U.S. patents and patent application publications cited on the attached Form PTO-1449 are submitted in accordance with 1276 OG 55 because the captioned application was filed after June 30, 2003.

Where the publication date of a listed document does not provide a month of publication, the year of publication of the listed document is sufficiently earlier than the effective U.S. filing date and any foreign priority date so that the month of publication is not in issue. Applicants have listed publication dates on the attached PTO-1449 based on information presently available to the undersigned. However, the listed publication dates

should not be construed as an admission that the information was actually published on the date indicated.

Applicants reserve the right to establish the patentability of the claimed invention over any of the information provided herewith, and/or to prove that this information may not be prior art, and/or to prove that this information may not be enabling for the teachings purportedly offered.

This statement should not be construed as a representation that a search has been made, or that information more material to the examination of the present patent application does not exist. The Examiner is specifically requested not to rely solely on the material submitted herewith.

This Information Disclosure Statement is being filed before the mailing date of a first Office Action on the merits. No statement or fee is required.

It is respectfully requested that the Examiner initial and return a copy of the enclosed PTO-1449, and indicate in the official file wrapper of the captioned patent application that the documents have been considered.

The U.S. Patent and Trademark Office is hereby authorized to charge any fee deficiency, or credit any overpayment, to our Deposit Account No. 19-0036.

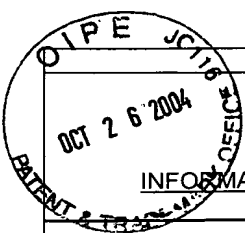
Respectfully submitted,

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FORM PTO-1449 INFORMATION DISCLOSURE STATEMENT	ATTY. DOCKET NO. 2236.0090000/JUK/SMW	APPLICATION NO. 10/784,806
	FIRST NAMED INVENTOR Kim, <i>et al.</i>	
	FILING DATE February 24, 2004	ART UNIT 1752

U.S. PATENT DOCUMENTS

EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUB-CLASS	FILING DATE
	AA1	US 4,491,628	01/01/85	Ito <i>et al.</i>			08/23/82
	AB1	US 5,968,713	10/19/1999	Nozaki <i>et al.</i>			07/18/97
	AC1						
	AD1						
	AE1						
	AF1						
	AG1						
	AH1						
	AI1						
	AJ1						
	AK1						

FOREIGN PATENT DOCUMENTS

EXAMINER INITIAL		DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUB-CLASS	TRANSLATION
	AL1						Yes No
	AM1						Yes No
	AN1						Yes No
	AO1						Yes No
	AP1						Yes No

OTHER (Including Author, Title, Date, Pertinent Pages, etc.)

	AR	1	Chang, F. C., "Potential Bile Acid Metabolites. 2. 3,7,12-Trisubstituted 5 β -Cholanic Acids," <i>J. Org. Chem.</i> 44:4567-4572, American Chemical Society (1979)
	AS	1	Hien, S., <i>et al.</i> , "Photoresist Outgassing at 157 nm Exposure," <i>Proc. SPIE</i> 4345:439-447, SPIE (2001)
	AT	1	

EXAMINER	DATE CONSIDERED
EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant.	